## Notice of References Cited

Application/Control No. 10/789,226	Applicant(s)/Patent Under Reexamination OGAWA ET AL.		
Examiner	Art Unit		
Leon-Viet Q. Nguyen	2611	Page 1 of 1	

## U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	Α	US-6,026,115 A	02-2000	Higashi et al.	375/148
*	В	US-6,175,587 B1	01-2001	Madhow et al.	375/148
*	C	US-2001/0028677 A1	10-2001	Wang et al.	375/148
*	D	US-2002/0131479 A1	09-2002	Butler et al.	375/147
*	E	US-6,507,605 B1	01-2003	Fukumoto et al.	375/152
*	F	US-6,549,565 B1	04-2003	Buehrer et al.	375/142
*	G	US-2003/0108091 A1	06-2003	Nishio et al.	375/148
*	Н	US-6,683,924 B1	01-2004	Ottosson et al.	375/343
*	-	US-7,027,421 B2	04-2006	Park et al.	370/335
*	J	US-7,106,785 B2	09-2006	Yoshida, Shousei	375/148
*	К	US-7,139,307 B2	11-2006	Takahashi, Hideyuki	375/148
	L	US-			
	М	US-			

## **FOREIGN PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N	WO02029996	10-2001	wo	Aldaz, Luis	h04B 1/707
	0					
	Р	·				
	Q				,	
_	R					
	s					
	т					

## NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	
	v	
	w	
	x	

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)

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